

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. .... 10/094,580  
Priority Filing Date ..... March 6, 2002  
 Inventor ..... Cem Basceri et al.  
 Assignee ..... Micron Technology, Inc.  
Priority Group Art Unit ..... 2818  
Priority Examiner ..... David Nhu  
 Attorney's Docket No. .... MI22-2407  
 Title: Plasma Enhanced Chemical Vapor Deposition Method of Forming a  
 Titanium Silicide Comprising Layer (as Amended)

**PRELIMINARY AMENDMENT**

To: Mail Stop Patent Application  
 Commissioner for Patents  
 P. O. Box 1450  
 Alexandria, VA 22313-1450

**VIA EXPRESS MAIL**

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Please enter the following amendments prior to examining the above-identified application.

**AMENDMENTS**